



International Standard

ISO 22514-7

Statistical methods in process management — Capability and performance —

Part 7: Capability of measurement processes

AMENDMENT 1

*Méthodes statistiques dans la gestion de processus — Aptitude et
performance —*

Partie 7: Aptitude des processus de mesure

AMENDEMENT 1

**Second edition
2021-08**

**AMENDMENT 1
2024-01**



COPYRIGHT PROTECTED DOCUMENT

© ISO 2024

All rights reserved. Unless otherwise specified, or required in the context of its implementation, no part of this publication may be reproduced or utilized otherwise in any form or by any means, electronic or mechanical, including photocopying, or posting on the internet or an intranet, without prior written permission. Permission can be requested from either ISO at the address below or ISO's member body in the country of the requester.

ISO copyright office
CP 401 • Ch. de Blandonnet 8
CH-1214 Vernier, Geneva
Phone: +41 22 749 01 11
Email: copyright@iso.org
Website: www.iso.org

Published in Switzerland

Foreword

ISO (the International Organization for Standardization) is a worldwide federation of national standards bodies (ISO member bodies). The work of preparing International Standards is normally carried out through ISO technical committees. Each member body interested in a subject for which a technical committee has been established has the right to be represented on that committee. International organizations, governmental and non-governmental, in liaison with ISO, also take part in the work. ISO collaborates closely with the International Electrotechnical Commission (IEC) on all matters of electrotechnical standardization.

The procedures used to develop this document and those intended for its further maintenance are described in the ISO/IEC Directives, Part 1. In particular, the different approval criteria needed for the different types of ISO document should be noted. This document was drafted in accordance with the editorial rules of the ISO/IEC Directives, Part 2 (see www.iso.org/directives).

ISO draws attention to the possibility that the implementation of this document may involve the use of (a) patent(s). ISO takes no position concerning the evidence, validity or applicability of any claimed patent rights in respect thereof. As of the date of publication of this document, ISO had not received notice of (a) patent(s) which may be required to implement this document. However, implementers are cautioned that this may not represent the latest information, which may be obtained from the patent database available at www.iso.org/patents. ISO shall not be held responsible for identifying any or all such patent rights.

Any trade name used in this document is information given for the convenience of users and does not constitute an endorsement.

For an explanation of the voluntary nature of standards, the meaning of ISO specific terms and expressions related to conformity assessment, as well as information about ISO's adherence to the World Trade Organization (WTO) principles in the Technical Barriers to Trade (TBT), see www.iso.org/iso/foreword.html.

This document was prepared by Technical Committee ISO/TC 69, *Applications of statistical methods*, Subcommittee SC 4, *Applications of statistical methods in product and process management*.

Any feedback or questions on this document should be directed to the user's national standards body. A complete listing of these bodies can be found at www.iso.org/members.html.

STANDARDSISO.COM : Click to view the full PDF of ISO 22514-7:2021/Amd 1:2024

Statistical methods in process management — Capability and performance —

Part 7: Capability of measurement processes

AMENDMENT 1

6.2.3.3

Replace the last row in Table 6 by the following:

		$u_{TA} = T - 20\text{ °C} \cdot u_{\alpha} \cdot l$ where T is the average temperature during the measurement; u_{α} is the uncertainty on the coefficient of expansion; l is the observed value for length measurement.
--	--	---

6.2.3.6.3

Replace the first formula by the following:

$$u_{TA} = |T - 20\text{ °C}| \cdot u_{\alpha} \cdot l$$

9.2

Replace the fourth and fifth paragraph by the following:

The capability of a measurement system can be expressed as a capability index C_{MS} .

$$C_{MS} = C_{MS_{min}} \cdot Q_{MS_{min}} \cdot \frac{(U-L)}{2 \cdot k \cdot u_{MS}} = \frac{4}{3} \cdot 0,15 \cdot \frac{(U-L)}{2 \cdot k \cdot u_{MS}} = 0,2 \cdot \frac{(U-L)}{2 \cdot k \cdot u_{MS}}$$

The capability of a measurement process can be expressed as a capability index C_{MP} .

$$C_{MP} = C_{MP_{min}} \cdot Q_{MP_{min}} \cdot \frac{(U-L)}{2 \cdot k \cdot u_{MP}} = \frac{4}{3} \cdot 0,30 \cdot \frac{(U-L)}{2 \cdot k \cdot u_{MP}} = 0,4 \cdot \frac{(U-L)}{2 \cdot k \cdot u_{MP}}$$

9.3

Replace the fifth and sixth paragraph up to before the formula with the following:

There are several ways to estimate the manufacturing process dispersion Δ in the following priority:

- manufacturing process dispersion determined according to ISO 22514-1 and ISO 22514-2
- manufacturing process dispersion calculated from the experiment described in clause 6.2.3.2
- manufacturing process spread and process location estimated from historical data of similar processes

See details in the following paragraphs.

The manufacturing process dispersion is preferably determined according to ISO 22514-1 and ISO 22514-2 using a minimum sample size of 100.

Replace the two paragraphs after Figure 5 by the following:

If an upper one-sided specification limit is given, the capability indices and performance ratios are calculated as:

$$C_{MS} = 0,2 \cdot \frac{C_p \cdot \Delta_U}{k \cdot u_{MS}} \quad C_{MP} = 0,4 \cdot \frac{C_p \cdot \Delta_U}{k \cdot u_{MP}}$$

$$Q_{MS} = \frac{k \cdot u_{MS}}{C_p \cdot \Delta_U} \quad Q_{MP} = \frac{k \cdot u_{MP}}{C_p \cdot \Delta_U}$$

If a lower one-sided specification limit is given, the capability indices and performance ratios are calculated as

$$C_{MS} = 0,2 \cdot \frac{C_p \cdot \Delta_L}{k \cdot u_{MS}} \quad C_{MP} = 0,4 \cdot \frac{C_p \cdot \Delta_L}{k \cdot u_{MP}}$$

$$Q_{MS} = \frac{k \cdot u_{MS}}{C_p \cdot \Delta_L} \quad Q_{MP} = \frac{k \cdot u_{MP}}{C_p \cdot \Delta_L}$$